

REMARKS/ARGUMENTS

Claims 1, 9, 10 and 12-14 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Chau in view of Pey; claims 2-8 and 11 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Pey as applied to claims 1, 9, 10 and 12-14, and further in view of Wolf.

Claim 1 was amended. Claim 1 comprises the limitations of depositing, on a portion of the first surface, a material that will react with the semiconductor layer to form a silicide portion adjacent said nitride spacer, removing the material that does not react with the portion of the first surface, and etching the nitride spacer subsequent to the removing of the material that does not react with a portion of the first surface.

The Chau patent describes forming a silicon nitride spacer (in Fig. 3G as described by the examiner in the office Action dated 12/03/2003) but does not describe etching the silicon nitride spacer subsequent to removing material used to form the silicide. The Pey patent describes in col. 6, lines 5-22 a process for removing unreacted metal using a 1:1:5 mixture of ammonia peroxide. This chemical will remove Ti/TiN but will not remove nitride as incorrectly stated by the examiner in Office Action dated 12/03/2003. The Pey patent does not teach etching the nitride sidewall subsequent to the removal of the material. Claim 1 as amended is therefore allowable over the Chau patent and the Pey patent under 35 U.S.C. 103(a). Furthermore, claims 2-14 depend on claim 1 and contain all the limitations of claim 1. Claims 2-14 are therefore also allowable over the Chau and Pey patents in addition to these patents combined with the Wolf reference.

In light of the above, it is respectfully submitted that the present application is in condition for allowance, and notice to that effect is respectfully requested.

While it is believed that the instant response places the application in condition for allowance, should the Examiner have any further comments or suggestions, it is

respectfully requested that the Examiner contact the undersigned in order to expeditiously resolve any outstanding issues.

To the extent necessary, Applicants petition for an Extension of Time under 37 CFR 1.136. Please charge any fees in connection with the filing of this paper, including extension of time fees, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668.

Respectfully submitted,



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